



Docket No.: 543822004700  
(PATENT)

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

In re Patent Application of:  
Siegfried SCHWARZL et al.

Application No.: 10/812,411

Confirmation No.: 1274

Filed: March 30, 2004

Art Unit: 1763

For: EUV LITHOGRAPHY SYSTEM AND CHUCK  
FOR RELEASING RETICLE IN A VACUUM  
ISOLATED ENVIRONMENT

Examiner: K. A. Moore

**AMENDMENT AFTER FINAL ACTION UNDER 37 C.F.R. 1.116**

MS AF  
Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

Sir:

**INTRODUCTORY COMMENTS**

In response to the final Office Action dated November 22, 2006, please amend this application as follows.

**Amendments to the Claims** are reflected in the listing of claims which begins on page

2.

**Remarks/Arguments** begin on page 6 of this paper.

DO NOT ENTER 3/15/07